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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No. : **10/040,042** Confirmation No. **1835**
Applicant : **Wei-Yu Su**
Filed : **November 7, 2001**
TC/A.U. : **1746**
Title : **Method for Reduction of Photomask Defects**

Docket No. : **N1085-90003**
Customer No. : **08933**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

**CERTIFICATE OF MAILING,
37 C.F.R. §1.8(a)**
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22313-1450

Richard A. Paikoff
Richard A. Paikoff, Reg. No. 34,892

6/8/04
Date

AMENDMENT AND RESPONSE

Sir:

In response to the Office Action of March 9, 2004, please amend the above-identified application as follows:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 4 of this paper.

Amendments to the Drawings begin on page 8 of this paper and include both an attached replacement sheet and an annotated sheet showing changes.

Remarks begin on page 9 of this paper.